

REMARKS

In accordance with this amendment, claim 43 has been amended to include a range of values for the width of the mesoscale channels referred to therein. Support for the amendment to claim 43 is provided in the present specification at page 5, first paragraph.

Claim 53 has been amended by specifying "depth" in place of "at least one channel dimension". Support for this amendment to claim 53 is provided in the present specification at page 5, first paragraph and page 18, first paragraph.

Claim 54 has been amended to recite that the channels are fabricated in the substrate layer by wet chemical etching, which is a fabrication technique described in the paragraph bridging pages 16-17 of the present specification.

Consequential amendments have been made in claims 50, 51, 59, 76, 78, 82-84 and 91.

Entry of the present amendment is hereby requested. These claim amendments do not introduce new matter into the application. All of these claim amendments are fairly based on the originally filed application.

Early and favorable consideration of the application as now amended is respectfully requested.

Respectfully submitted,

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